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Contents

vii *Conference Committee*

OPTICAL MANUFACTURING I

12221 03 **Prototyping, replication, and metrology of freeform optical micro-components (Invited Paper)**
[12221-1]

OPTICAL MANUFACTURING II

12221 07 **Strategies for improving ultrafast laser stress figuring range and resolution** [12221-5]

12221 08 **Differential phase measuring deflectometry for on-machine metrology of ultrafast laser stress figuring** [12221-6]

12221 09 **Solarization effects in optical glass from UV to blue** [12221-9]

12221 0A **Using ISO environmental standards in an ISO 10110 format drawing** [12221-11]

12221 0B **Novel micro-textured film offers promise in universal handling of optics** [12221-12]

NAUTILUS SPACE TELESCOPE I

12221 0C **Nautilus Space Observatory: a very large aperture space telescope constellation enabled by scalable optical manufacturing technologies (Invited Paper)** [12221-13]

12221 0D **Type 2 longitudinal chromatic aberration from a high-harmonic MODE lens and color corrector**
[12221-14]

12221 0E **Fabrication, assembly, and testing of a MODE lens color corrector** [12221-15]

12221 0F **Stray light analysis and testing of a MODE lens telescope** [12221-16]

NAUTILUS SPACE TELESCOPE II

- 12221 0G **Precision glass molding technology for the MODE lens telescope** [12221-17]
- 12221 0H **Autonomous closed-loop control for multi-segmented optic aligning and assembly** [12221-18]
- 12221 0I **Progress towards alignment of Multi-Order Diffractive Engineered (MODE) lens segments using the Kinematically-Engaged Yoke System (KEYS) for optical performance testing** [12221-19]
- 12221 0J **Initial testing of a MODE lens telescope** [12221-20]

OPTICAL TESTING I

- 12221 0K **Generalized surface reconstruction and fringe analysis through phase measuring deflectometry** [12221-24]
- 12221 0L **Conical null-screen design for evaluating a biconical surface using a smartphone-based corneal topographer** [12221-26]
- 12221 0M **Influence of lens and perspective distortion on optical surface metrology instrumentation** [12221-27]
- 12221 0N **Measurement of non-uniform AR-coated surfaces using an optical coordinate measurement machine with coating effect error compensation** [12221-38]

OPTICAL TESTING II

- 12221 0Q **Absolute distance measurement using polarization-based spectral-domain interferometer with dual reference path** [12221-22]
- 12221 0R **An interferometric method for simultaneous measurement of thickness, refractive index, and surface profile of a silicon wafer** [12221-23]
- 12221 0S **Picometer-range characterization of LAM dynamics with whole-field LDV** [12221-39]

OPTICAL TESTING III

- 12221 0T **Scanning Shack-Hartmann sensor for wavefront measurements on freeform optics** [12221-28]
- 12221 0U **Reconstruction of optical wavefronts with parallel registration algorithms** [12221-30]

- 12221 0V **Measurement of inner centration of an asphere with computer generated holograms compared to an optical profiler** [12221-52]
- 12221 0W **Quantifying the validity conditions of the Beckmann-Kirchhoff scattering model** [12221-31]

OPTICAL TESTING IV

- 12221 0Y **Evaluating SMR positioning with an autostigmatic microscope** [12221-33]
- 12221 10 **Absolute characterization of gravity sag for light-weighted optics** [12221-35]
- 12221 11 **Measurements of the critical parameters in high aspect ratio semiconductor microstructures such as deep trenches, deep holes, and through silicon vias** [12221-54]

POSTER SESSION

- 12221 12 **Parametric circular aperture segmentation formalism** [12221-8]
- 12221 13 **CTE effects of CVD silicon carbide cladding of a silicon carbide optic** [12221-10]
- 12221 17 **3D reconstruction of aerodynamic airfoils using computer stereo vision** [12221-45]
- 12221 19 **Improved quantitative testing of a nonsymmetric convex surface using a conical null screen** [12221-48]
- 12221 1A **Single-shot intraocular lens surface measurement with the GelSight topography system** [12221-49]
- 12221 1B **On-machine laser spot diagnostics by scanning linear image sensor for maskless lithography system** [12221-50]
- 12221 1C **Corneal topography using dynamic point shifting method in quadrangular OLED's prism** [12221-47]

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